

Enhancing Surface and Thin Film Analysis Through In-Situ Complementary Raman Spectroscopy

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Advanced materials present ever increasing challenges to the analytical scientist. Composite materials built from nanostructures or ultra-thin films, often with complex chemistries present, are now required in a broad range of applications, and achieving full characterization is rarely managed using only one analysis method. To maintain confidence in the results from the utilization of several different methods, it is advantageous to be able to perform experiments on the same platform. Ideally, this should be without having to move the sample, removing the need for additional registration or processing to ensure that the data is being collected from the same position.

For surface analysis, it has been common for many years to incorporate related analysis techniques onto the same instrument. For example, X-ray photoelectron spectroscopy (XPS) systems are commonly equipped with UV light sources to facilitate investigation of additional properties of materials via ultra-violet photoelectron spectroscopy (UPS). The ion source that is typically used for sample cleaning and depth profiling can also be used for low energy ion scattering (LEIS or ISS), providing more surface sensitive elemental composition information than can be delivered from XPS alone. The addition of a focused electron source enables Auger electron spectroscopy (AES) which provides surface sensitive composition at higher spatial resolution than XPS can offer. With the exception of ISS, all these routine additional analysis techniques are electron spectroscopy based and offer similar information.

We have recently integrated further instrumentation onto a standard XPS system. The integrated system has combined a Raman spectrometer with a micro-focused, monochromated XPS system. The focal points are aligned such that data can be acquired from the same point simultaneously, and that the sizes of the analysis areas are comparable in size. Chemical modifications of the material can be easily determined and quantified with XPS. Raman offers a fast way of determining the quality and conformity of the material, and direct compound identification. The greater depth of field of the Raman spectrometer also offers bulk information to complement the surface sensitive XPS data.

In this presentation we will discuss the strengths of this combined, in-situ approach to surface analysis, illustrated with examples from a range of applications.